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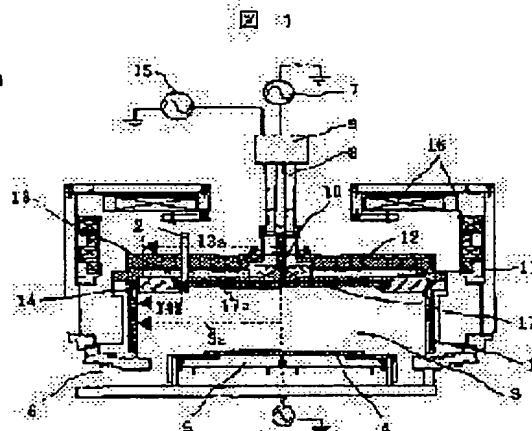
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(54) PLASMA PROCESSING SYSTEM

(57)Abstract:

PROBLEM TO BE SOLVED: To provide a plasma processing system realizing a high density, high uniformity plasma over a wide parameter region in a plasma generation system employing a high frequency of VHF or UHF band and a magnetic field.

SOLUTION: The plasma processing system comprises an antenna and a radiation port for supplying a high frequency of VHF or UHF band to a processing chamber, and means for forming a magnetic field in the processing chamber wherein the ratio of the radius of the antenna and the effective length of the radiation port is set in the range of 0.4-1.5.



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